

FIG 1

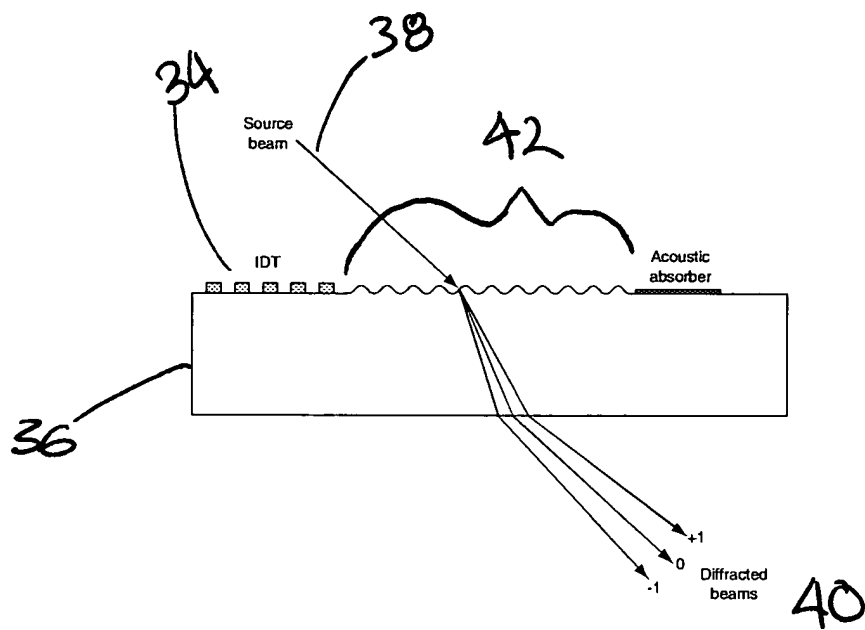
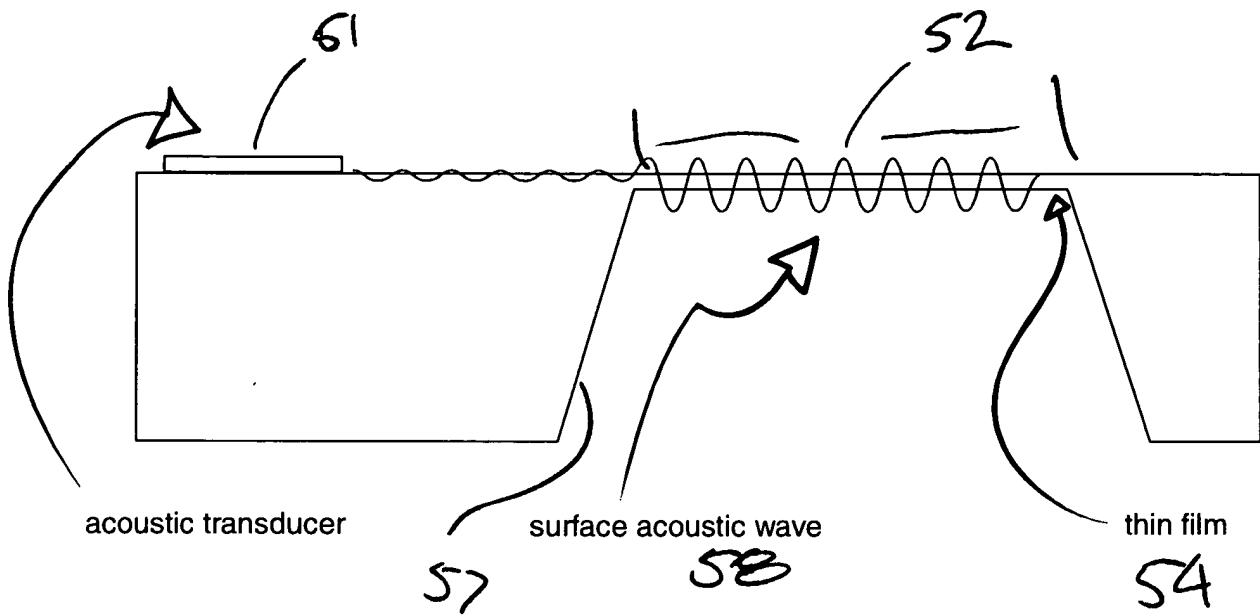


FIG 2

FIG. 3 is a schematic diagram of a surface acoustic wave device. The device includes a substrate 50, a thin film 54, and an acoustic transducer 61. A surface acoustic wave 52 is shown propagating along the surface of the thin film 54. The wave is represented by a wavy line. The acoustic transducer 61 is shown as a rectangular block on the surface of the substrate 50. The thin film 54 is shown as a rectangular block on the surface of the substrate 50. The surface acoustic wave 52 is shown propagating along the surface of the thin film 54. The wave is represented by a wavy line. The acoustic transducer 61 is shown as a rectangular block on the surface of the substrate 50. The thin film 54 is shown as a rectangular block on the surface of the substrate 50.



50

FIG 3

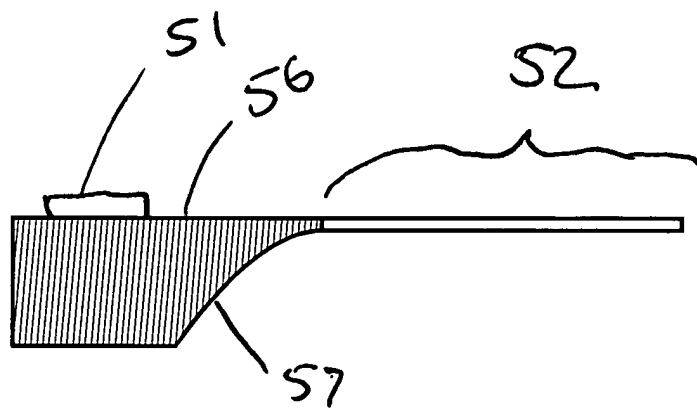


FIG 3b

FIG. 4a is a perspective view of a mold assembly 60. The mold assembly 60 includes a base 62 and a plurality of cavities 64. Each cavity 64 is defined by a pair of opposed walls 66 and a bottom wall 68. The cavities 64 are arranged in a row. The mold assembly 60 is used to form a plurality of articles 70. Each article 70 is formed by a pair of opposed walls 72 and a bottom wall 74. The articles 70 are arranged in a row. The mold assembly 60 is used to form the articles 70 by injecting a material into the cavities 64. The material is then cured to form the articles 70. The mold assembly 60 is used to form the articles 70 in a continuous manner.

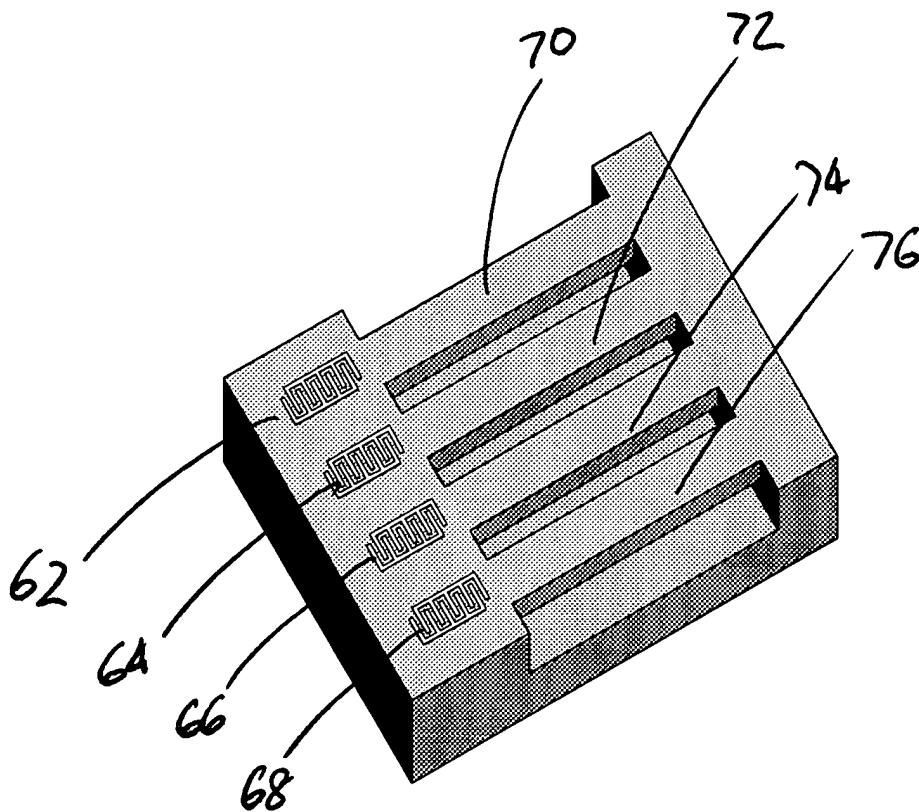


FIG 4a

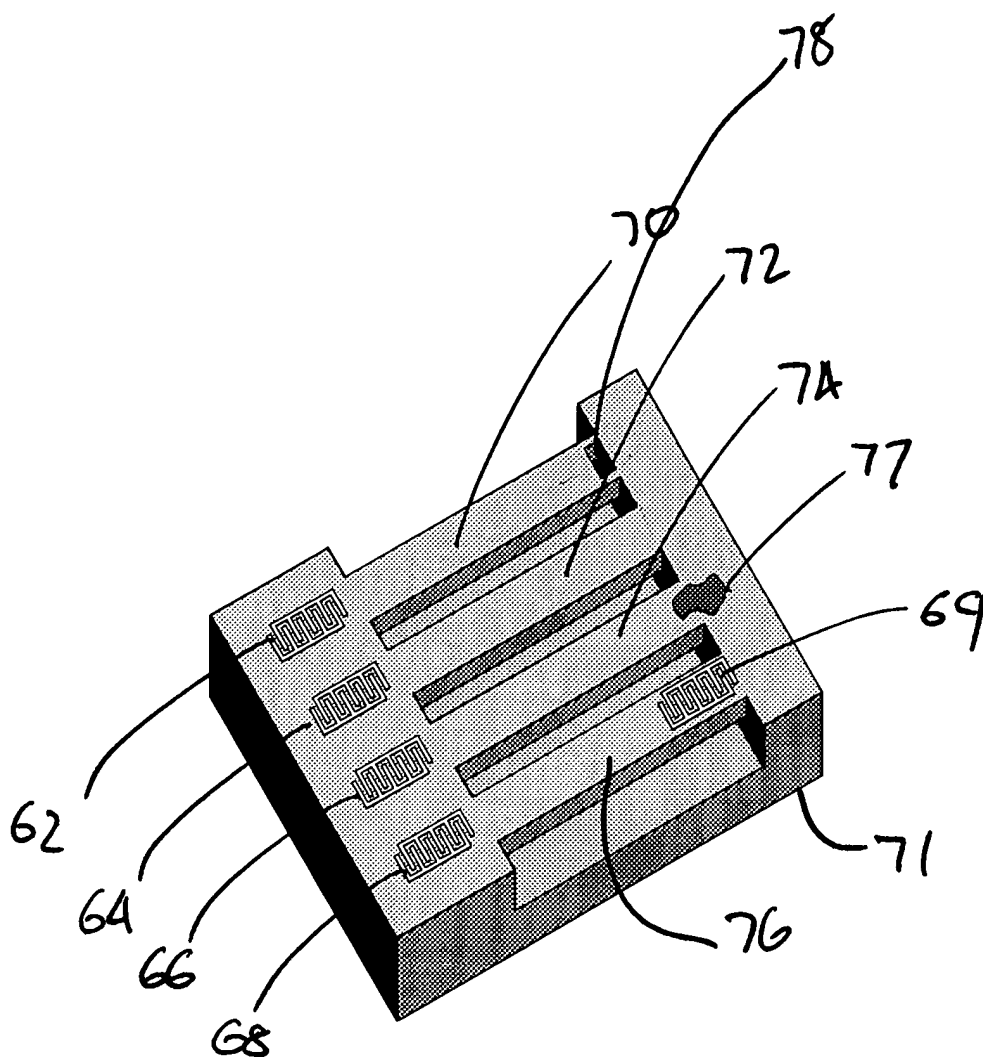


FIG 4b

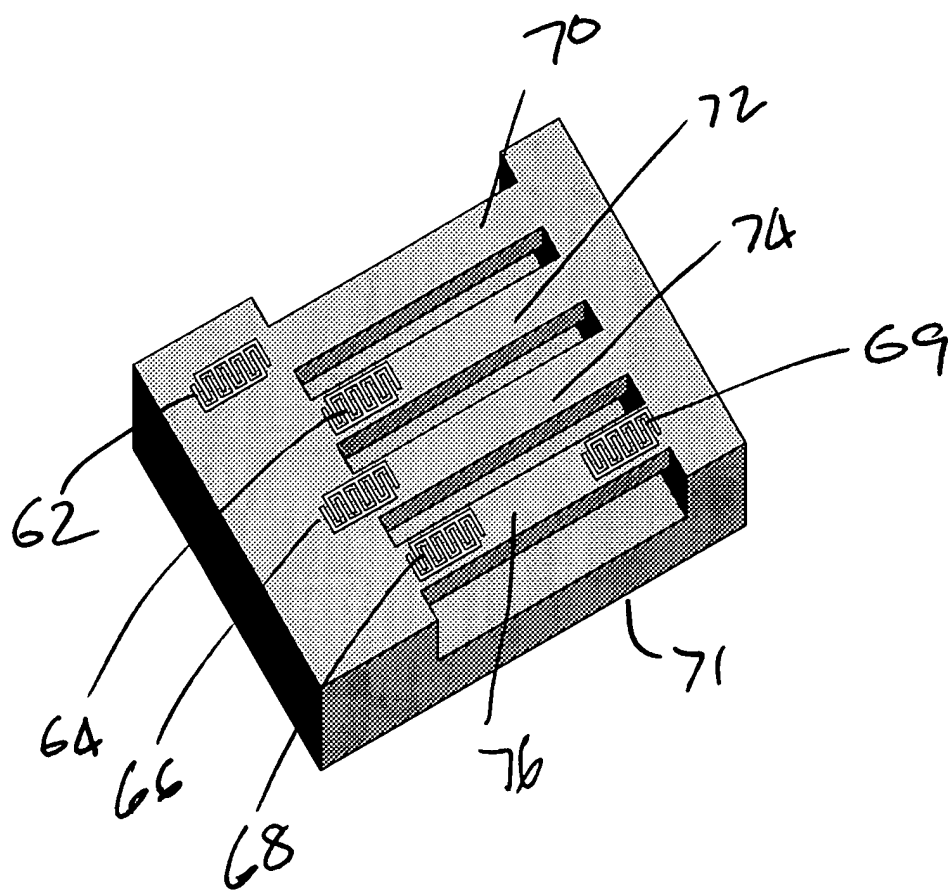


FIG 4c

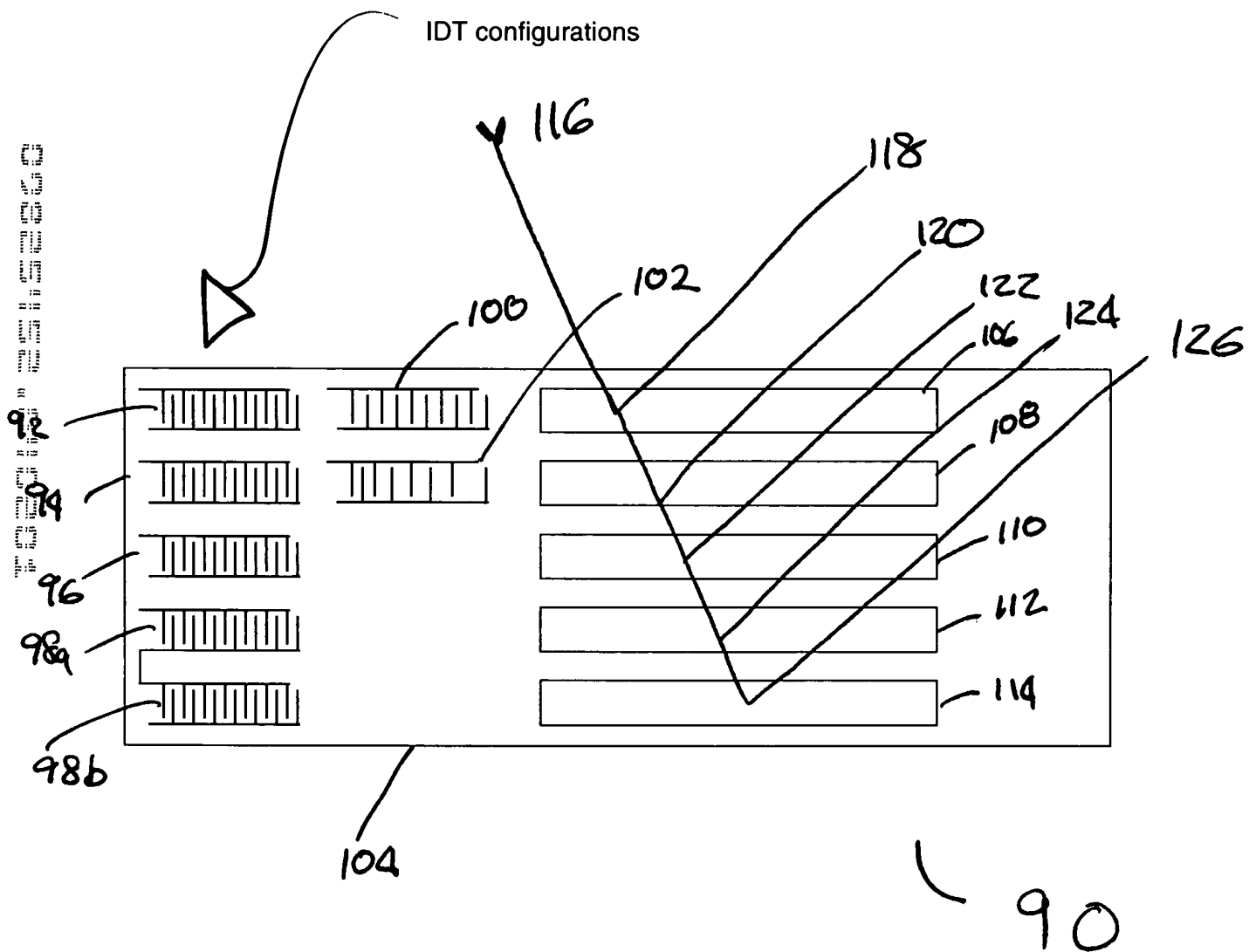
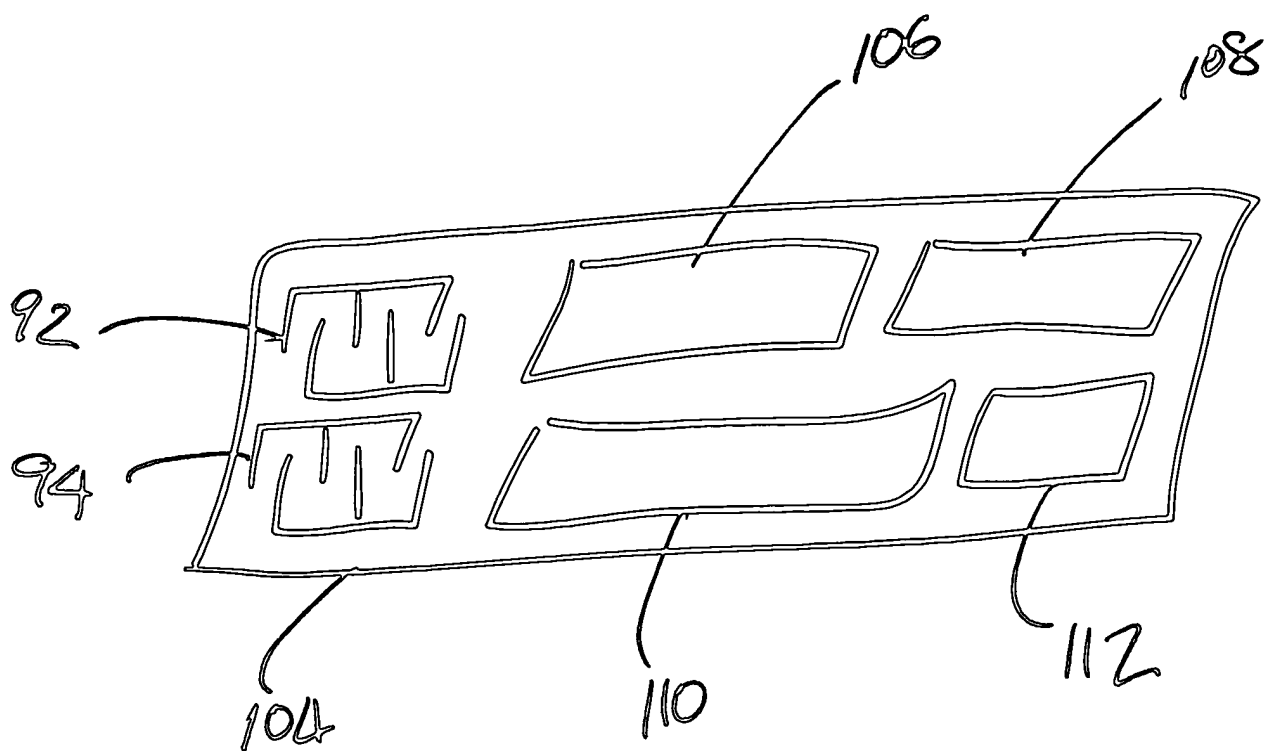


FIG 5a



FIG. 5B is a perspective view of the control panel 100 showing the control buttons 92, 94, 104, 106, 108, 110, and 112.



5B

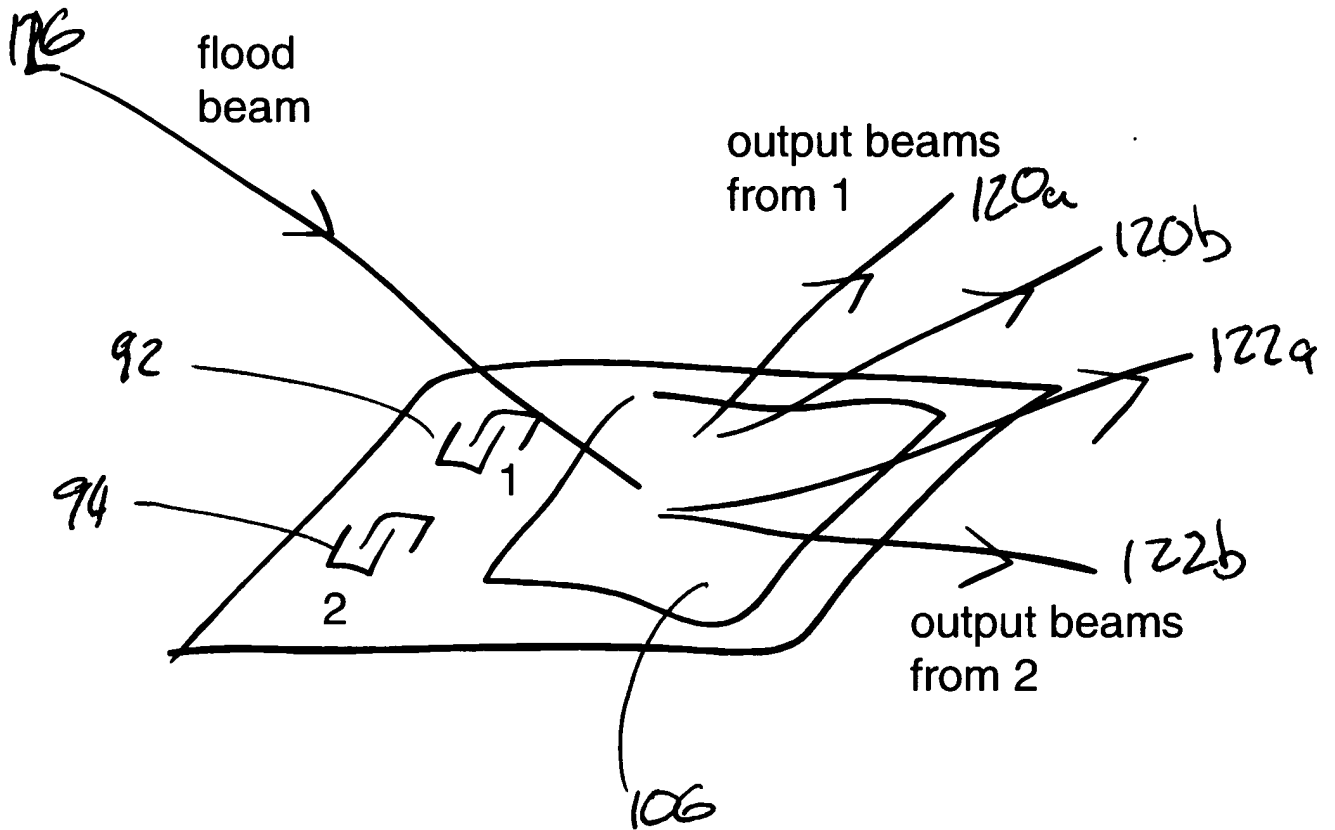


FIG 5C

multiple  
input  
beams

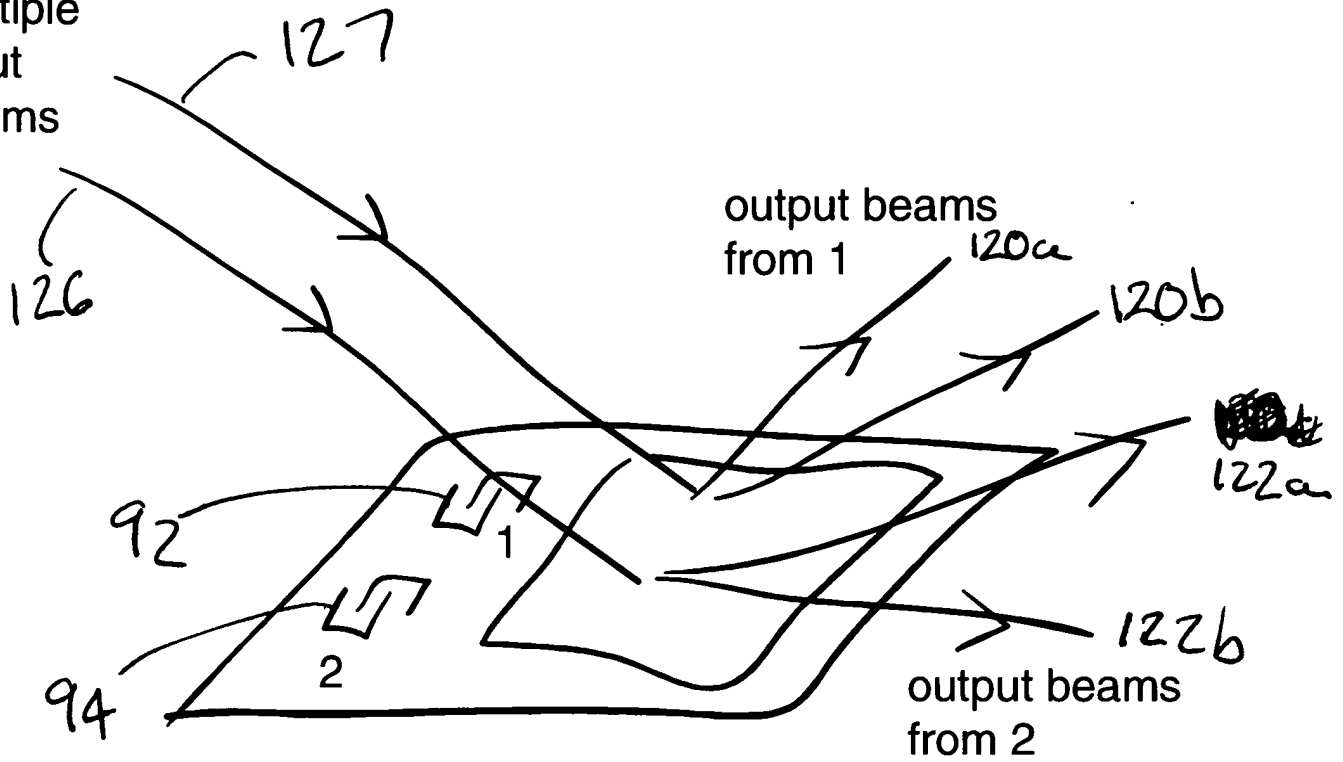


FIG 5d

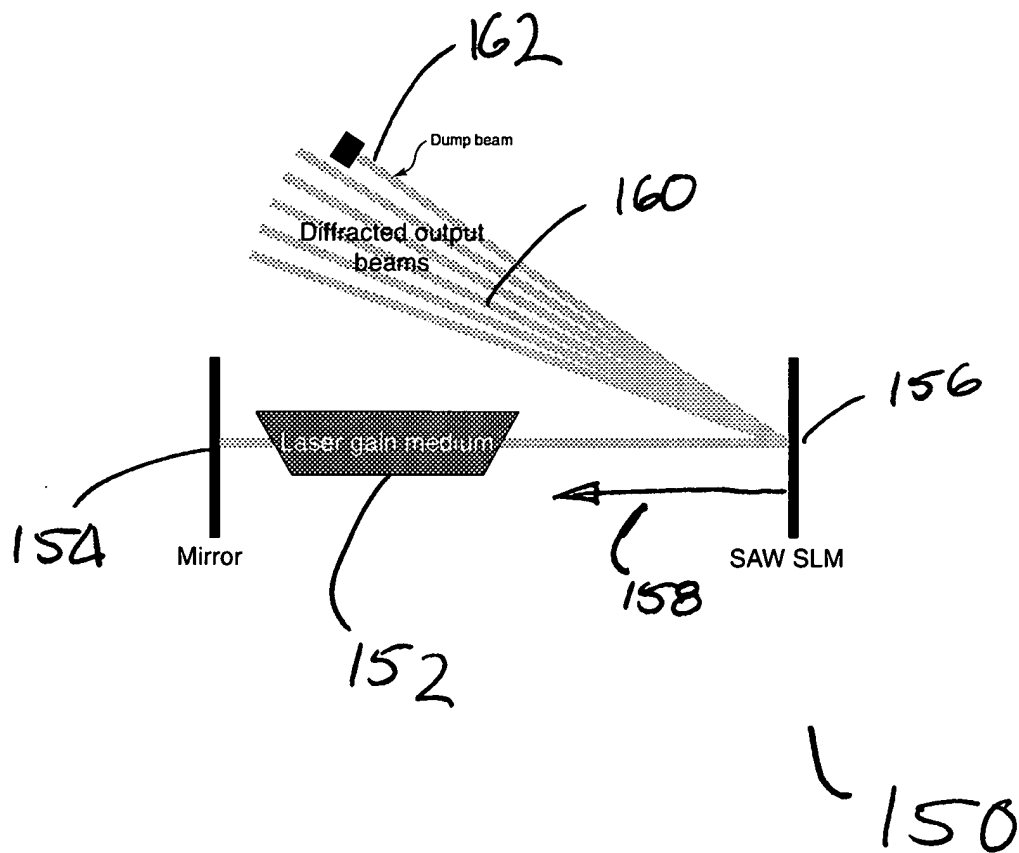


FIG 6

FIG. 7 is a perspective view of a fiber optic system 170. The system 170 includes a source 172, a collimating lens 174, a beam splitter 176, and receiving fibers 178. The source 172 includes source fibers 172a, 172b, and 172c. The collimating lens 174 includes collimating lenses 174a, 174b, and 174c. The beam splitter 176 includes beam splitters 176a, 176b, and 176c. The receiving fibers 178 include receiving fibers 178a, 178b, and 178c.

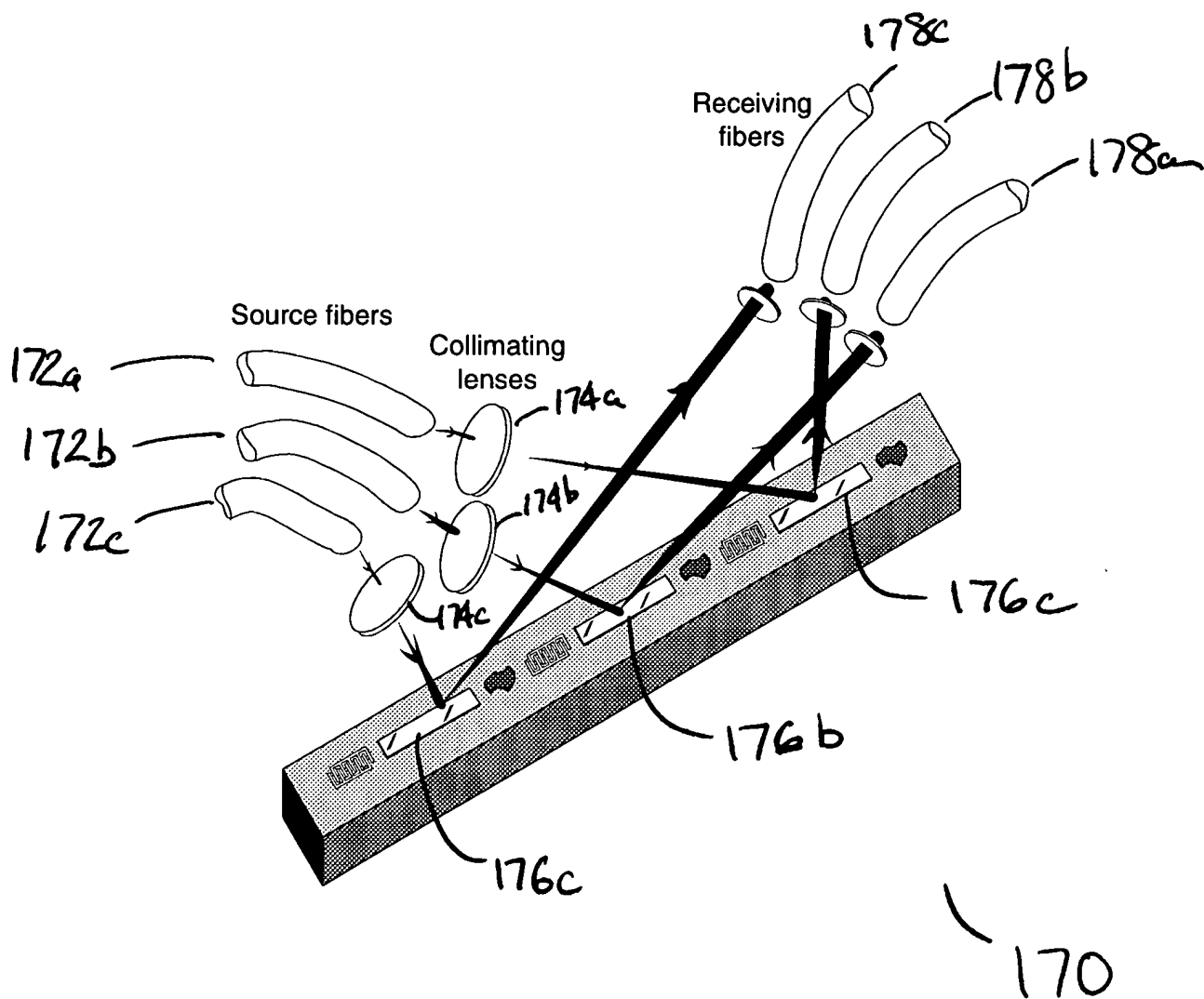
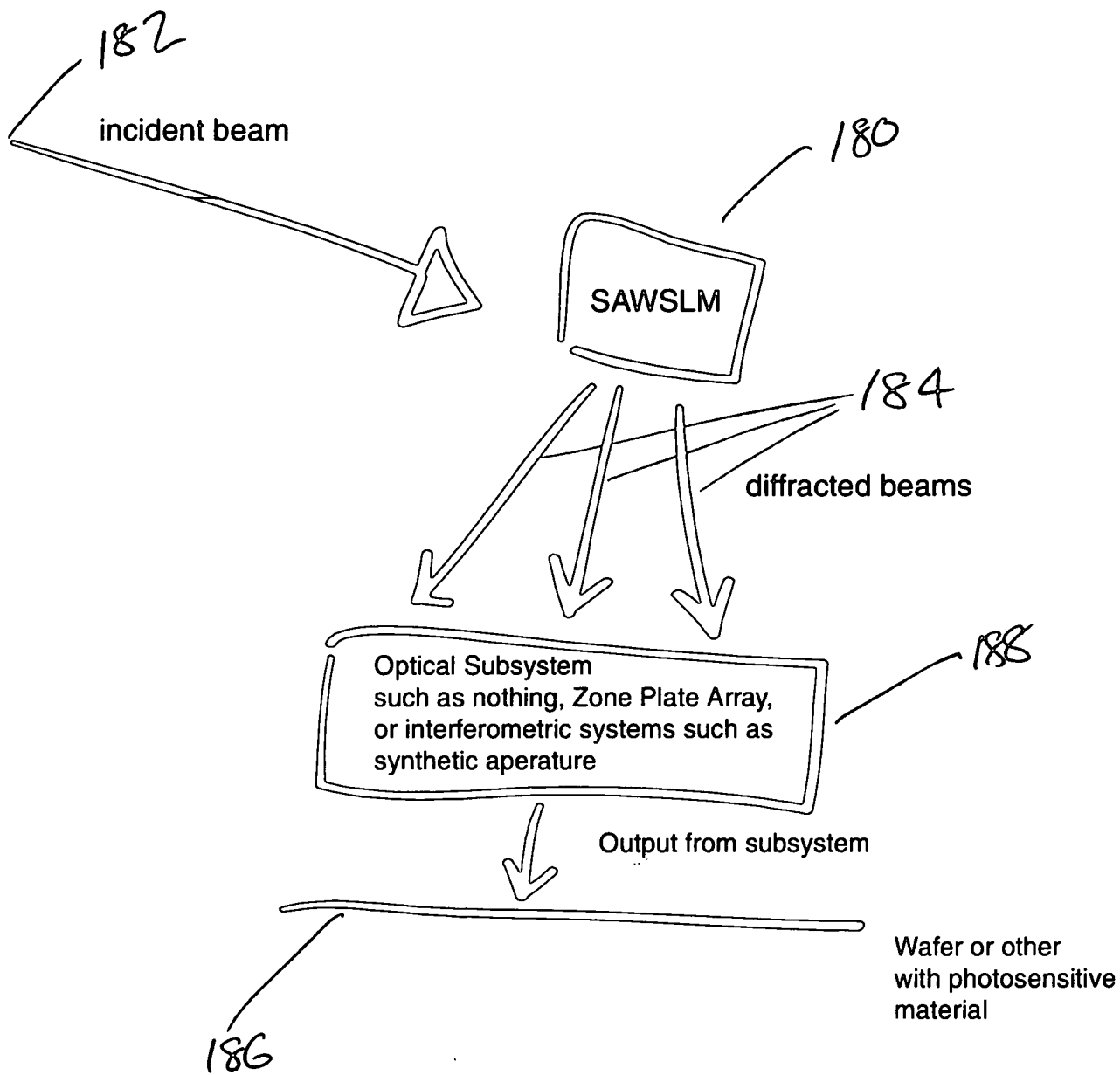


FIG 7

FIG. 8 is a schematic diagram of a SAW SLM as part of a lithographic system. The diagram shows an incident beam 182 entering a SAW SLM 180. The SAW SLM 180 is a rectangular block with the label "SAWSLM" inside. Three diffracted beams 184 emerge from the SAW SLM 180 and are directed towards an optical subsystem 188. The optical subsystem 188 is a rectangular block with the text "Optical Subsystem such as nothing, Zone Plate Array, or interferometric systems such as synthetic aperture" inside. An arrow labeled "Output from subsystem" points from the optical subsystem 188 to a wafer or other photosensitive material 186, which is represented by a horizontal line.



SAW SLM as part of Lithographic System

FIG 8

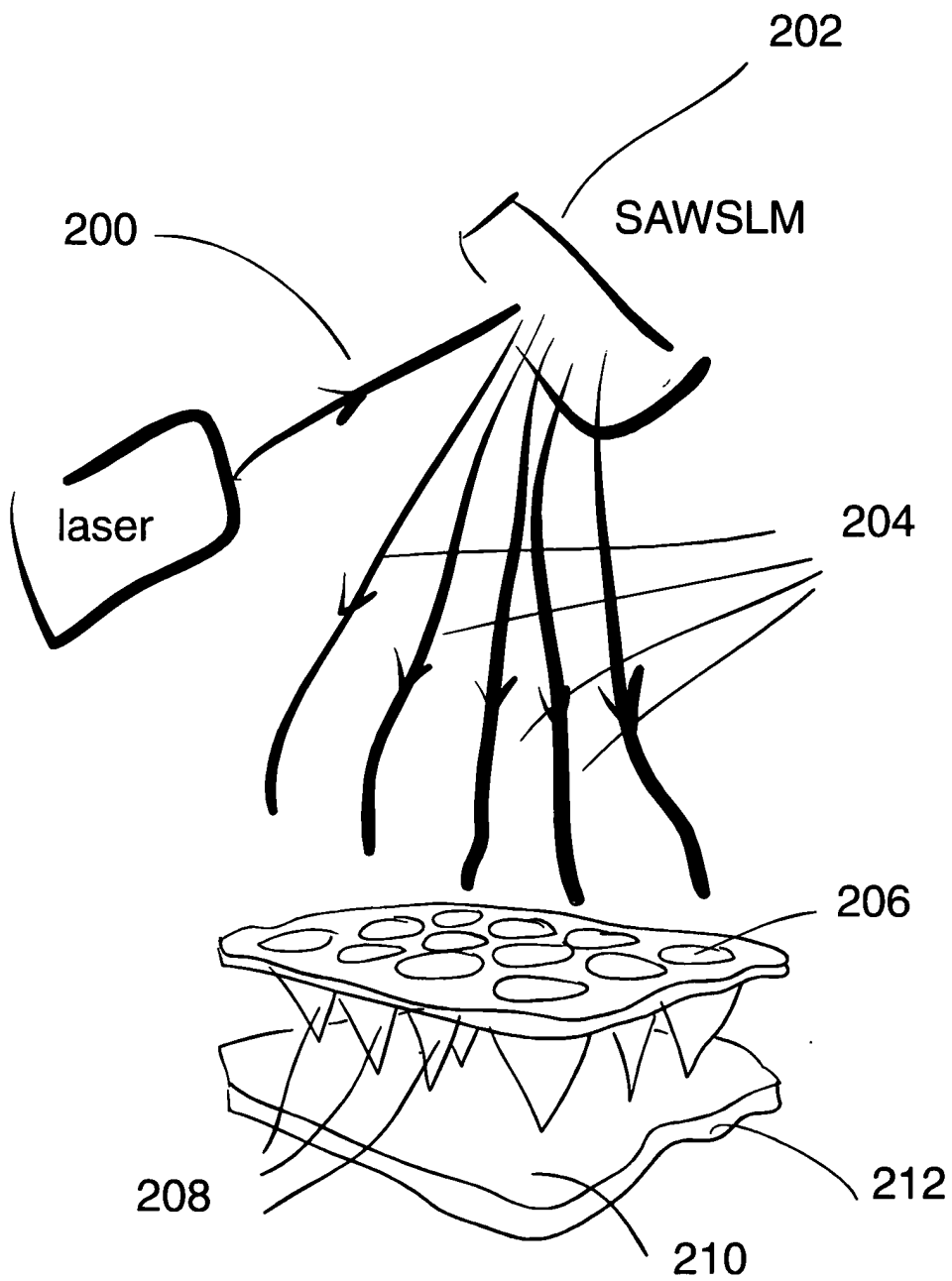


FIG 9

FIG. 10 is a schematic diagram of a device 220 for generating a source beam 228. The device 220 includes a substrate 222 and a layer 223. A source beam 228 is generated by the device 220. The source beam 228 is incident on a grating 232. The grating 232 has a period  $d_1$ . The source beam 228 is diffracted by the grating 232 into three diffracted beams 236, labeled -1, 0, and +1. The device 220 also includes a circuit 225 and a control unit 227. The control unit 227 is connected to the circuit 225. The circuit 225 includes a voltage source  $V$  and a current source  $I$ . The voltage source  $V$  is connected to the circuit 225. The current source  $I$  is connected to the circuit 225. The circuit 225 is connected to the substrate 222. The substrate 222 is connected to the layer 223. The layer 223 is connected to the grating 232. The grating 232 is connected to the source beam 228. The source beam 228 is incident on the grating 232. The grating 232 has a period  $d_1$ . The source beam 228 is diffracted by the grating 232 into three diffracted beams 236, labeled -1, 0, and +1. The device 220 also includes a circuit 225 and a control unit 227. The control unit 227 is connected to the circuit 225. The circuit 225 includes a voltage source  $V$  and a current source  $I$ . The voltage source  $V$  is connected to the circuit 225. The current source  $I$  is connected to the circuit 225. The circuit 225 is connected to the substrate 222. The substrate 222 is connected to the layer 223. The layer 223 is connected to the grating 232. The grating 232 is connected to the source beam 228. The source beam 228 is incident on the grating 232. The grating 232 has a period  $d_1$ . The source beam 228 is diffracted by the grating 232 into three diffracted beams 236, labeled -1, 0, and +1.

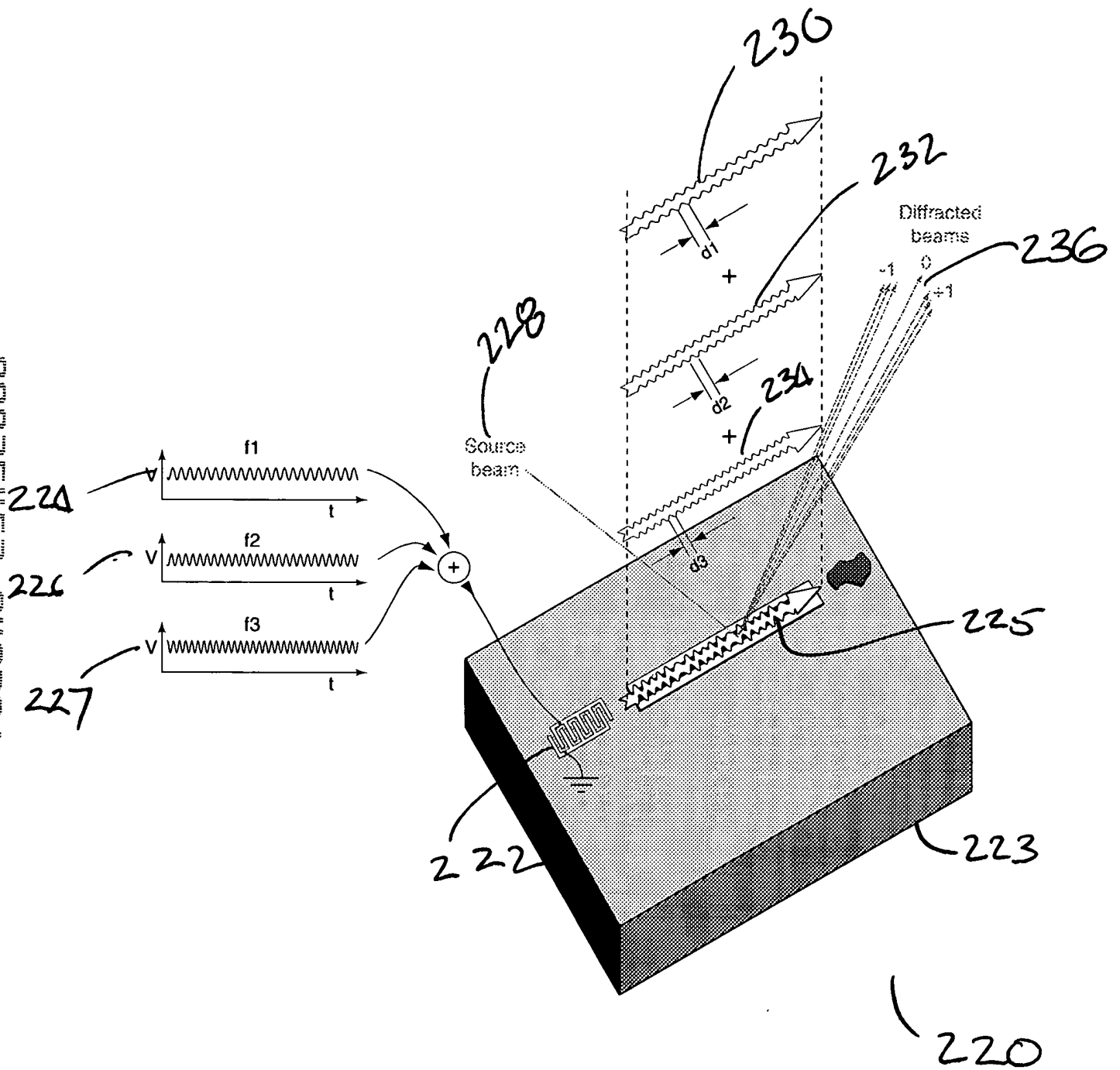


FIG 10



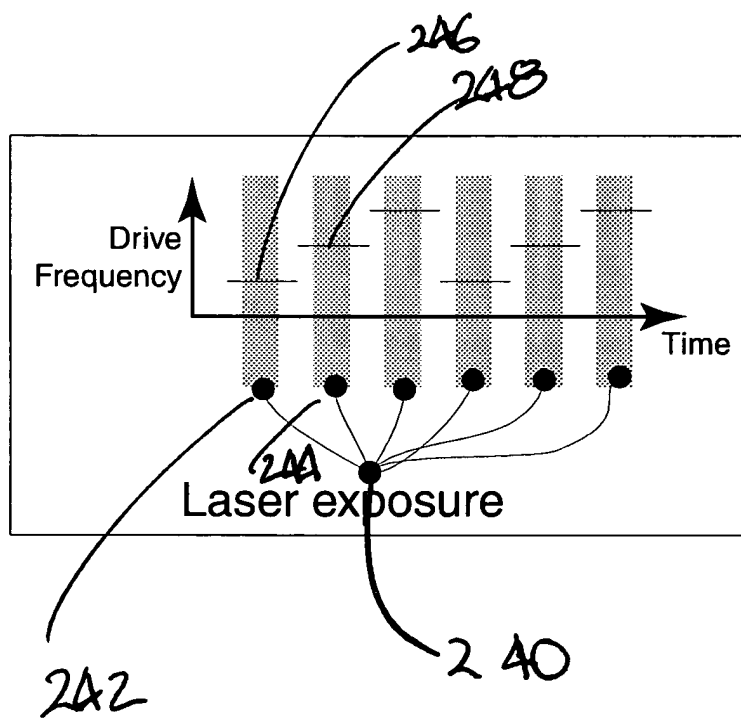


FIG 11

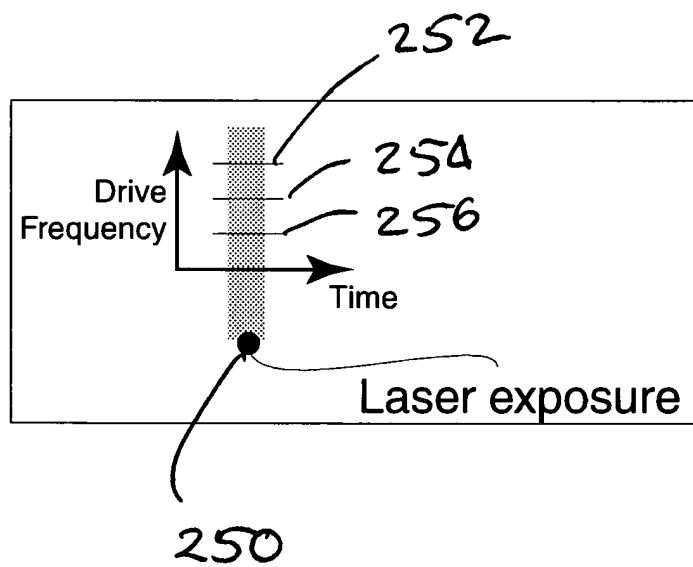
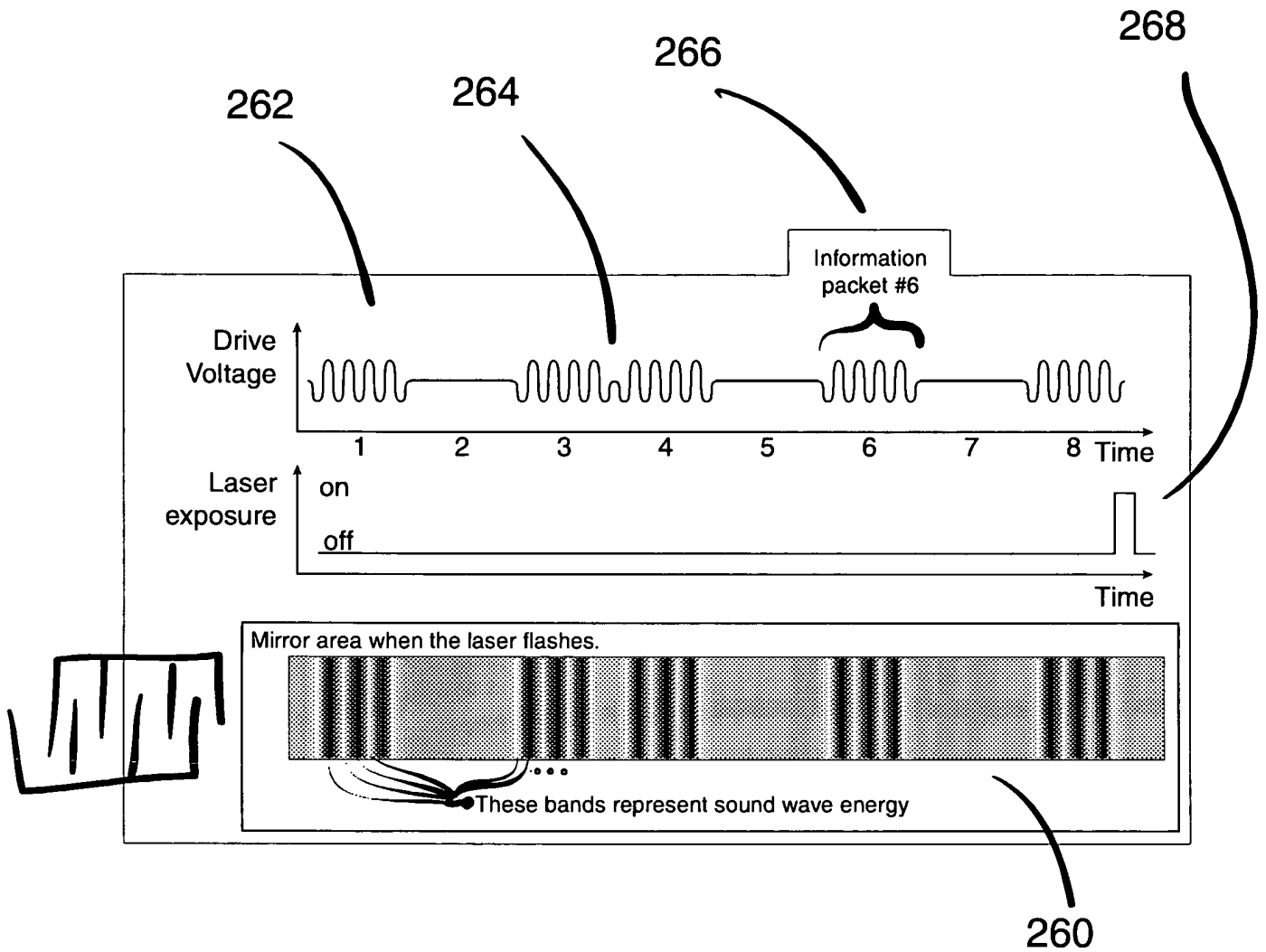
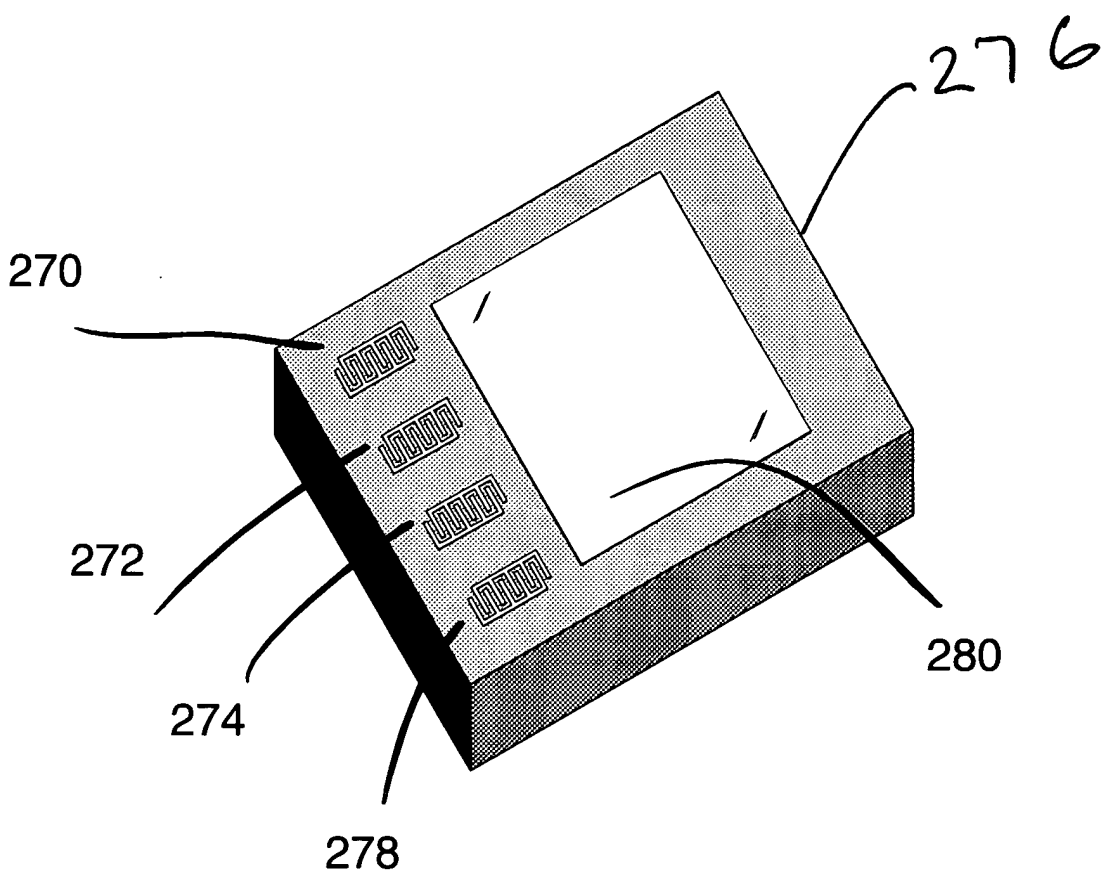


FIG 12

FIG. 13 is a schematic diagram of a system for recording sound wave energy on a mirror surface. The system includes a drive voltage source (262) connected to a mirror (260). The drive voltage source is configured to output a series of pulses (264) that correspond to the sound wave energy. The mirror (260) is configured to reflect the sound wave energy as a series of bands (266) on its surface. The bands (266) are formed by the interaction of the sound wave energy with the mirror surface. The system also includes a laser exposure source (268) that is configured to expose the mirror surface (260) to a laser beam. The laser exposure source is configured to output a series of pulses (264) that correspond to the sound wave energy. The laser exposure source is configured to output a series of pulses (264) that correspond to the sound wave energy. The laser exposure source is configured to output a series of pulses (264) that correspond to the sound wave energy.



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FIG. 14b

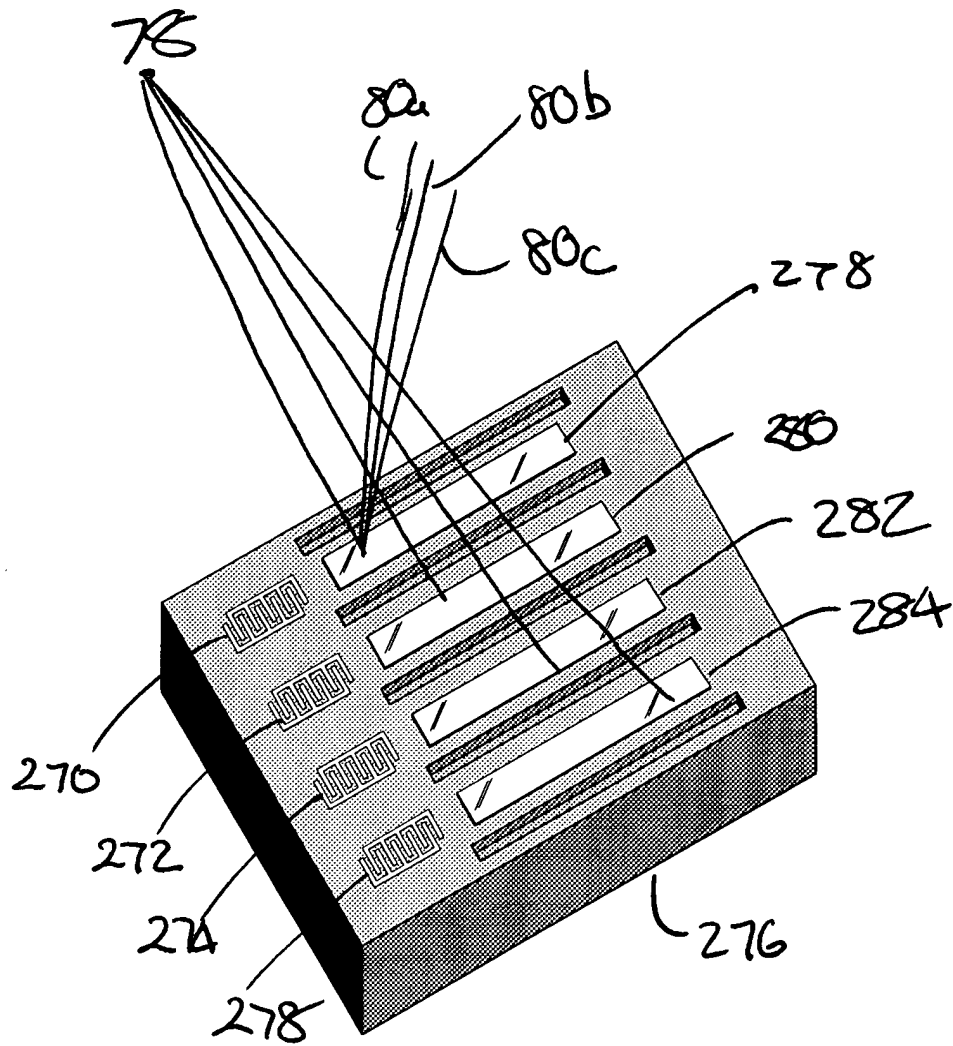


FIG 14b